

4. (Three Times Amended) A method of storing a silicon wafer in water, comprising the steps of preparing storage water, which is ultra pure water containing Cu at a concentration of 0.01 ppb or less, and storing a silicon wafer in the prepared storage water.

Rewrite claim 11 as follows:

11. (Twice Amended) A method of storing a silicon wafer in water according to Claim 24, wherein the step of storing the silicon wafer comprises storing the silicon wafer immediately after polishing.

Rewrite claim 12 as follows:

12. (Twice Amended) A method of storing a silicon wafer in water according to claim 4, wherein the step of preparing storage water includes using storage water containing a chelating agent.

Rewrite claim 21 as follows:

21. (Amended) A regulating method of a storage water used for storage of a silicon wafer in water, wherein the concentration of Cu in the storage water, which is ultra pure water, is regulated to 0.01 ppb or less.

Please add the following new claims:

--22. A storage water used for storage of a silicon wafer in water according to Claim 1, wherein the storage water contains a surfactant.

23. A method of storing a silicon wafer in water according to Claim 4, wherein the step of preparing storage water includes using storage water containing a surfactant.

24. A method of storing a silicon wafer in water according to Claim 23, wherein the step of storing a silicon wafer includes providing a silicon wafer having a hydrophobic surface.

25. A method of storing a silicon wafer in water according to Claim 23, wherein the step of storing a silicon wafer comprises storing the silicon wafer immediately after polishing.--